October 20 (Tue.), 2026

[Oral 04] Metrology & Inspection / Equipment / Process Diagnostics

15:35-16:35

International Conference Hall (B1F)

● Session Chair: Catharina Rudolph Fraunhofer (IZM-ASSID, Germany)

15:35-15:55 [Oral 04-1]	Robust CMP Topography Extraction via Adaptive Polynomial Selection Viorel Balan, Yorrick Exbrayat (Univ. Grenoble Alpes, France), and Sebastien Mermoz (STMicroelectronics, France)
15:55-16:15 [Oral 04-2]	Surface-Enhanced Particle Sizing and Raman Fingerprinting for Nanoscale Abrasive and Residue Detection in Critical CMP Processes Harvey Tang and Ali Altun (UNISERS AG, Switzerland)
16:15-16:35 [Oral 04-3]	Exploratory Data Analysis of Oscillatory Torque-Related Features in CMP Sensor Logs Associated with Slurry Formulation Kohei Noda and Hisashi Shinomura (JSR Corp., Japan)